EAST Search History

EAST Search History (Prior Art)

Ref#	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S67	26	(("5879862") or ("6380564") or ("6455870") or ("6509270") or ("6589857") or ("6627989") or ("7348212") or ("20030178626") or ("20030218179") or ("20040031967") or ("20040217362") or ("20050173692") or ("20080265366")).PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2011/06/03 10:50
S68	2	("6492661").PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2011/06/03 11:45
S69	560	(ohmic near contact) same (epi or epitaxial\$4) same (mirror or reflect\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/06/03 14:15
S70	2348	(seed near10 (adhesion or adhesive or barrier) near10 (electroplat\$4 or electro-plat\$4 or electro \$plat\$4))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/06/03 14:16
S71	244	((pattern\$4 or etch\$4) near10 (resist or photoresist or photo-resist or photo\$resist)) same (between or interpos\$4 or inter-pos\$4 or alternat\$4 or sandwich\$4) same (heat near2 (sink\$4 or spread\$4 or dissipat\$4 or releas\$4))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/06/03 14:19

S72	5	S69 and S70 and S71	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/06/03 14:21
\$73	62	("20010055324" "20020022286" "20020034835" "20020013279" "20020117681" "20020134985" "20020137243" "20020179910" "20030038284" "20030011667" "20030151357" "20030151357" "20030189215" "20040026709" "20040026709" "20040104395" "20040110395" "20040130037" "20040130037" "20040235210" "20050026399" "20050026399" "20050082555" "200500882555" "200500887884" "20050098792" "200500127397" "20050127397" "20060154390" "20060154390" "20060154390" "20060154391" "20060154393" "20060154393" "20060154393" "20060154393" "20060154393" "20060154393" "20060154391" "20060154393" "20060154392" "20060154393" "20060154390" "20060154390" "20060154390" "200601543	US-PGPUB; USPAT; USOCR	OR	SON	2011/06/03 14:48
		"6573537" "6627921"				

	***************************************	"6649437" "6677173" "6821804" "7338822"). PN. OR ("7763477"). URPN.				
S74	1044	(pattern\$4 or etch\$4) same (resist or photoresist or photo-resist or photo\$4 or photo\$1 same (heat near2 (sink\$4 or spread\$4 or dissipat\$4 or releas\$4))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/06/03 14:55
S75	7	S69 and S74	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/06/03 14:55
S76	166	S69 and ((pattern\$4 or etch\$4) same (resist or photoresist or photo-resist or photo\$resist))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/06/03 14:56
S77	161	S76 not S72	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/06/03 14:56
S78	39	("4445218" "5909459" "6107644").PN. OR ("6291839").URPN.	US-PGPUB; USPAT; USOCR	OR	ON	2011/06/03 15:07
S79	2819	(438/22).CCLS.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2011/06/03 15:12
S80	2647	(438/29). CCLS.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2011/06/03 15:12
S81	1606	(438/122).CCLS.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2011/06/03 15:12

S82	1166	(257/E33.001).CCLS.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2011/06/03 15:12
S83	308	(257/E33.075).CCLS.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2011/06/03 15:13
S84	5	(Tinggi near Technologies near Private near Limited). as.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/06/03 15:13
S85	743	(Kang near Xuejun).in. or (Wu near Daike).in. or (Perry near2 Robert).in. or (Yuan near Shu).in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/06/03 15:14
S86	743	S84 or S85	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/06/03 15:14
S87	13	S86 and ((ohmic near contact) same (epi or epitaxial\$4) same (mirror or reflect\$4))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/06/03 15:14

EAST Search History (Interference)

Ref#	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S90	7	((ohmic near contact) and (epi or epitaxial\$4) and (mirror or reflect\$4) and seed and (adhesion or adhesive or barrier) and (pattern\$4 or etch\$4) and (resist or photo-resist or photo \$resist)).clm.	US-PGPUB; USPAT; UPAD	OR	ON	2011/06/03 15:22

6/3/2011 4:31:51 PM

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